

le 'Exposur D s C ntr I T chniques f r Excim r las r Lith graphy'
by D. H. Tracy and F. Y. Wu and published in Pr c dings of th SPIE, Volum
922 (1988) pag 437-443, disclos s a scanning slit exposur device acc rding t
the pr amble in which the exp sur disc ntinuities have b n r duced. This
known device uses a defocused image of a normal slit as an instantaneous field
stop. The resulting defocus blur avoids the high spatial frequencies common to
a sharply imaged slit, and reduces the sensitivity of the exposure device to
banding. A disadvantage of the known device is that the amount of induced
defocus depends on the radiation distribution at the exit window. Devices
having an adjustable radiation distribution must therefore also have an
adjustable defocus.

It is an object of the invention to provide a scanning-slit exposure device
which has a reduced dependence of the induced blur on the radiation
distribution at the exit window.